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Dated: November 20, 2002

Signature

(Reza Mollaaghababa)

Docket No.: 101328-0148

(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Theodore H. Fedynyshyn

Application No.: 09/512,942

Group Art Unit: 1752

Filed: February 25, 2000

Examiner: J. Chu

For: ENCAPSULATED INORGANIC RESISTS

**AMENDMENT AND RESPONSE UNDER 37 CFR 1.116**

BOX AF  
Commissioner for Patents  
Washington, DC 20231

Dear Sir:

Applicant thanks the Examiner for extending to Applicant's representatives the opportunity to discuss the outstanding issues in the present application during a telephonic interview on October 23, 2002. In view of this discussion, in response to the final Office Action mailed from the United States Patent and Trademark Office on June 20, 2002, Applicant provides the attached Declaration under 37 C.F.R. 1.132, and the following remarks to establish that the invention distinguishes patentably over the cited reference. Accordingly, reconsideration and allowance of the application are respectfully requested.

**REMARKS**

The present invention provides photosensitive resist materials, useful in lithography, that include colloidal particles that significantly increase the plasma etch sensitivity of the photoresist materials. More particularly, the invention provides positive photoresist compositions that include encapsulated inorganic core particles, and that are base soluble upon activation by radiation.

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